

AirSentry® II

Multi-point Monitoring System



The AirSentry® II Multi-point Monitoring System is the most advanced airborne molecular contamination (AMC) monitor available, utilizing sensitive and responsive ion mobility spectrometry to detect and characterize airborne molecular contamination from multiple locations within a cleanroom. The system features a 16- or 30-point manifold sampling system and an on-board industrial computer with secure software and communications.

In modern cleanroom manufacturing areas, process tools are often spread over large cleanroom areas and multiple floors. Air handlers recirculate the majority of air within a cleanroom which can easily spread molecular contamination to unwanted areas, negatively impacting process steps located away from actual contamination sources. The AirSentry II AMC Monitoring System provides a central and cost-effective monitoring station that allows for rapid contamination detection, as well as monitoring sequences to cover a wide number of sample points spread across a facility. A critical part of a strategic AMC monitoring program.

BENEFITS

- Low cost-per-sample point
- Detects multiple AMC compounds, as specified by the user
- Programmed monitoring to detect AMC events and trends
- Compact size
- Versatile configuration of testing locations

FEATURES

- Monitors up to 30 sample locations
- Features AirSentry II ion mobility spectrometry (IMS) sensors—sensitive, reliable, repeatable
- Detection of low concentrations of acids, amines, ammonia and chlorides
- Calibrations traceable to the National Institute of Standards and Technology (NIST)
- Real-time graphical software
- Industrial PC for robust and reliable operation in production environments
- Slide-out keyboard and display for convenient interface

APPLICATIONS

- Multi-point cleanroom and process bay monitoring
- Baseline and qualification of AMC levels in new cleanrooms
- Analysis and quantification of chemical filter efficiency
- Characterization of AMC contribution from makeup and recirculation air



Without measurement there is no control

Sample point options	16 or 30 Channels
Analyzer options	NH ₃ , Amines, Acids, Chlorides
Analyzer ranges	0 - 50 ppb _v
Sample tube length (max.)	75 m
Power	120 VAC or 230 VAC
CDA requirements	10 LPM, 40 psig input, < -76 °F (< -60 °C) dew point, no particles > 50 µm, hydrocarbon-free
Vacuum	< 33 kPa (absolute)
Weight	Depends on analyzer configuration
Dimensions (H x W x L)	46 x 23 x 30 in (117 x 58 x 76 cm)
Communication	Ethernet (OPC)

Strategies for AMC contamination monitoring fall into three general categories:

1. Real-Time:

Real-time monitors are used continuously in the most critical locations, such as photolithography, where even sub-ppb levels of contamination degrade process performance and negatively impact yield.

2. Near Real-Time:

Near real-time monitors consist of a multi-port sampling scheme to sample a large number of locations on a periodic basis (2 – 3 times per day).

3. Off-Line:

Off-line monitoring generally is the process of manually collecting an air sample over a 6 – 24 hour period; laboratory analysis is performed at some later date, with results returned in 7 – 10 business days.

A robust AMC monitoring process uses a combination of all three strategies with a near real-time technique providing the majority of information. The data from the near real-time analyzer often triggers the subsequent use of either real-time or off-line techniques in order to provide more detailed time-based or composition-based information. This allows for minimum monitoring costs as real-time and off-line techniques are more expensive on a per sample point basis over the lifetime of the monitoring period. In summary, near real-time monitoring through the use of the AirSentry II AMC Monitoring System is the foundation upon which robust and capable AMC monitoring programs and strategies are built.

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